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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Jung et al.

Serial No.: 10/789,055

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Group Art Unit: 1752

Examiner: Sin J. Lee

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October 7, 2005

James P. Zeller Reg. No. 28,491

AMENDMENT "A"

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Please amend this application as follows:

the amendments to the claims section begins on page 2 of this paper;

the remarks section begins on page 6 of this paper.